

# Beom Yong Kim

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/9603762/publications.pdf>

Version: 2024-02-01

6  
papers

134  
citations

1478505

6  
h-index

1872680

6  
g-index

6  
all docs

6  
docs citations

6  
times ranked

151  
citing authors

#	ARTICLE	IF	CITATIONS
1	Enhanced Ferroelectric Properties in Hf <sub>0.5</sub> Zr <sub>0.5</sub> O <sub>2</sub> Films Using a HfO <sub>0.61</sub> N <sub>0.72</sub> Interfacial Layer. <i>Advanced Electronic Materials</i> , 2022, 8, 2100042.	5.1	24
2	Polarizing and depolarizing charge injection through a thin dielectric layer in a ferroelectricâ€“dielectric bilayer. <i>Nanoscale</i> , 2021, 13, 2556-2572.	5.6	26
3	Improved ferroelectricity in Hf <sub>0.5</sub> Zr <sub>0.5</sub> O <sub>2</sub> by inserting an upper HfO <sub>x</sub> N <sub>y</sub> interfacial layer. <i>Applied Physics Letters</i> , 2021, 119, .	3.3	8
4	Fieldâ€“induced Ferroelectric Hf <sub>1-x</sub> Zr <sub>x</sub> O <sub>2</sub> Thin Films for Highâ€“k Dynamic Random Access Memory. <i>Advanced Electronic Materials</i> , 2020, 6, 2000631.	5.1	19
5	Study of ferroelectric characteristics of Hf <sub>0.5</sub> Zr <sub>0.5</sub> O <sub>2</sub> thin films grown on sputtered or atomic-layer-deposited TiN bottom electrodes. <i>Applied Physics Letters</i> , 2020, 117, .	3.3	19
6	A Comparative Study on the Ferroelectric Performances in Atomic Layer Deposited Hf <sub>0.5</sub> Zr <sub>0.5</sub> O <sub>2</sub> Thin Films Using Tetrakis(ethylmethylamino) and Tetrakis(dimethylamino) Precursors. <i>Nanoscale Research Letters</i> , 2020, 15, 72.	5.7	38